

S1813 – run sheet

Kayaku Advanced Materials (Microposit brand; datasheet originally published by Rohm and Haas Electronic Materials / later Dow Electronic Materials)

nanyte.com/photoresists/s1813 · last updated 2026-07-26

Thickness: 1.0–1.9 μm

Softbake: 115 °C · 60 s · hotplate

Exposure dose: 150 mJ/cm² @ 436 nm

Develop: Developer MICROPOSIT MF-319 metal-ion-free (MIF) developer family (stated as optimized for); also compatible with metal-ion-bearing (MIB) MICROPOSIT developers. Individual test figures cite MF-31 (i.e. MF-319) and MF-321 by name. · Dilution Test conditions in Tables 4, 7 and 8 use MF-319/MF-321 diluted 1:10 ("MF-31/10", "MF-321/10"); Table 1 does not name a specific developer or dilution. · Method Double Spray Puddle (DSP) at 21°C in all cited process-condition tables